## RECEIVED CENTRAL FAX CENTER

## IN THE CLAIMS

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Please amend the claims of the present application under the provisions of 37 C.F.R. §1.121(c), as indicated below:

1.(Currently amended): Glass-ceramics having an average liner thermal expansion coefficient within a range of  $0.0 \pm 0.2 \times 10^{-7}$ / °C within a temperature range from 0° C to 50° C, having difference between the maximum value and the minimum value of  $\Delta L/L$  of  $10 \times 10^{-7}$  or below, and comprising SiO<sub>2</sub>, Al<sub>2</sub>O<sub>3</sub> and P<sub>2</sub>O<sub>5</sub> with the total amount thereof in mass % being within a range from 86.7% to 89.0% and further comprising CaO in an amount of 0.5 mass % or more, wherein the ratio of P<sub>2</sub>O<sub>5</sub> to Al<sub>2</sub>O<sub>3</sub> in mass % is within a range from 0.270 to 0.33 and the ratio of P<sub>2</sub>O<sub>5</sub> to SiO<sub>2</sub> in mass % is within a range from 0.1230 to 0.1450.

## 2. (Cancelled)

- 3. (Currently amended) Glass-ceramics baving an average liner thermal expansion coefficient within a range of  $0.0 \pm 0.1 \times 10^{-7}$ / °C within a temperature range from 0° C to 50° C, having difference between the maximum value and the minimum value of  $\Delta L/L$  of 8 x  $10^{-7}$  or below, and comprising SiO<sub>2</sub>, Al<sub>2</sub>O<sub>3</sub> and P<sub>2</sub>O<sub>5</sub> with the total amount thereof in mass % being within a range from 86.7% to 89.0% [[%]] and further comprising CaO in an amount of 0.5 mass % or more, wherein the ratio of P<sub>2</sub>O<sub>5</sub> to Al<sub>2</sub>O<sub>3</sub> in mass % is within a range from 0.270 to 0.33 and the ratio of P<sub>2</sub>O<sub>5</sub> to SiO<sub>2</sub> in mass % is within a range from 0.1230 to 0.1450.
- 4. (Cancelled)
- 5. (Original): Glass-ceramics as defined in claim 1 wherein surface roughness (Ra) (arithmetic mean roughness) is 3Å or below.

- 6. (Original): Glass-ceramics as defined in claim 1 wherein an average crystal grain diameter of precipitating crystal phase or phases is within a range from 50 nm to 90 nm.
- 7. (Original): Glass-ceramics as defined in claim 1 which comprise  $\beta$ -quartz ( $\beta$ -SiO<sub>2</sub>) and/or  $\beta$ -quartz solid solution ( $\beta$ -SiO<sub>2</sub> solid solution) as a predominant crystal phase.
- 8. (Original): Glass-ceramics as defined in claim 1 which are free of PbO,  $Na_2O$ ,  $K_2O$  and  $B_2O_3$ .
- 9. (Original): Glass-ceramics as defined in claim 1 obtained by heat treating, for crystallization, a base glass which comprises, in mass %,

SiO<sub>2</sub> 53-57% P<sub>2</sub>O<sub>5</sub> 7.0-8.5% and Al<sub>2</sub>O<sub>3</sub> 23-26%

and is substantially free of PbO, Na<sub>2</sub> O, K<sub>2</sub>O and B<sub>2</sub>O<sub>3</sub>, said glass-ceramics comprising  $\beta$ -quartz ( $\beta$ -SiO<sub>2</sub>) and/or  $\beta$ -quartz solid solution ( $\beta$ -SiO<sub>2</sub> solid solution) as a predominant crystal phase.

- 10. (Original): Glass-ceramics as defined in claim 9 comprising, in mass %, Li<sub>2</sub>O within a range of 3.5-4.5%.
- 11. (Previously presented): Glass-ceramics as defined in claim 10 comprising, in mass %,

CaO 0.5-1.5% and MgO 0.5-1.5% and/or ZnO 0.1-1.5% and/or BaO 0.5-1.5% and/or TiO 2 1.5-3.0% and/or ZrO2 1.0-3.0% and/or

 $As_2O_3$ 0.5-1.0%.

- 12. (Original): Glass-ceramics as defined in claim 1 wherein the maximum temperature of the heat treatment for crystallization is within a range from 750°C to 800°C.
- 13. (Previously presented): A mask for lithography using glass-ceramics as defined in claim 1.
- 14. (Previously presented): An optical system reflecting mirror for lithography using glass-ceramics as defined in claim 1.
- 15. (Previously presented): A wafer stage or a reticle stage for lithography using glassceramics as defined in claim 1.
- 16. (Previously presented): A component part of a precision instrument using glassceramics as defined in claim 1.
- 17. (Original): Glass-ceramics as defined in claim 3 wherein surface roughness (Ra) (arithmetic mean roughness) is 3Å or below.
- 18. (Original): Glass-ceramics as defined in claim 3 wherein an average crystal grain diameter of precipitating crystal phase or phases is within a range from 50 nm to 90 nm.
- 19. (Original): Glass-ceramics as defined in claim 3 which comprise β-quartz (β-SiO<sub>2</sub>) and/or, β -quartz solid solution (β -SiO<sub>2</sub> solid solution) as a predominant crystal phase.
- (Original): Glass-ceramics as defined in claim 3 which are free of PbO, Na₂O, K₂O and B<sub>2</sub>O<sub>3</sub>.
- 21. (Original): Glass-ceramics as defined in claim 3 obtained by heat treating, for crystallization, a base glass which comprises, in mass %,

SiO <sub>2</sub>	53-57%
$P_2O_5$	7.0-8.5% and
Al <sub>2</sub> O <sub>3</sub>	23-26%

and is substantially free of PbO,  $Na_2$  O,  $K_2$  O and  $B_2$ O3, said glass-ceramics comprising  $\beta$  -quartz ( $\beta$  -SiO<sub>2</sub>) and/or  $\beta$  -quartz solid solution ( $\beta$  -SiO<sub>2</sub> solid solution) as a predominant crystal phase.

- 22. (Original): Glass-ceramics as defined in claim 21 comprising, in mass %, Li<sub>2</sub>O within a range of 3.5-4.5%.
- 23. (Previously presented): Glass-ceramics as defined in claim 22 comprising, in mass %,

CaO	0.5-1/5% and
MgO	0.5-1.5% and/or
$Z_{\rm In}O$	0.1-1.5% and/or
BaO	0.5-1.5% and/or
TiO <sub>2</sub>	1.5-3.0% and/or
$ZrO_2$	1.0-3.0% and/or
As <sub>2</sub> O <sub>3</sub>	0.5-1.0%.

- 24. (Original): Glass-ceramics as defined in claim 3 wherein the maximum temperature of the heat treatment for crystallization is within a range from 750° C to 800° C.
- 25. (Previously presented): A mask for lithography using glass-ceramics as defined in claim 3.
- 26. (Previously presented): An optical system reflecting mirror for lithography using glass-ceramics as defined in claim 3.

- 27. (Previously presented): A wafer stage or a reticle stage for lithography using glassceramics as defined in claim 3.
- 28. (Previously presented): A component part of a precision instrument using glassceramics as defined in claim 3.
- 29. (Original): Glass-ceramics as defined in claim 2 obtained by heat treating, for crystallization, a base glass which comprises, in mass %

53-57% SiO<sub>2</sub>

 $P_2O_5$ 7.0-8.5% and

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 $Al_2O_3$ 23-26%

and is substantially free of PbO, Na<sub>2</sub>O, K<sub>2</sub>O and B<sub>2</sub>O<sub>3</sub>, said glass-ceramics comprising β quartz (β -SiO<sub>2</sub>) and/or β -quartz solid solution (β -SiO<sub>2</sub> solid solution) as a predominant crystal phase.

- 30. (Original): Glass-ceramics as defined in claim 29 comprising, in mass %, Li<sub>2</sub>O within a range of 3.5-4.5%.
- 31. (Previously presented): Glass-ceramics as defined in claim 30 comprising, in mass %,

CaO 0.5-1.5% and MgO 0.5-1.5% and/or ZnO 0.1-1.5% and/or BaO 0.5-1.5% and/or TiO<sub>2</sub> 1.5-3.0% and/or ZrO<sub>2</sub> 1.0-3.0% and/or  $As_2O_3$ 0.5-1.0%.

32. (Original): Glass-ceramics as defined in claim 4 obtained by heat treating, for

crystallization, a base glass which comprises, in mass %,

SiO<sub>2</sub> 53-57%

 $P_2O_5$  7.0-8.5% and

Al<sub>2</sub>O<sub>3</sub> 23-26%

and is substantially free of PbO, Na<sub>2</sub>O, K<sub>2</sub>O and B<sub>2</sub>O<sub>3</sub>, said glass-ceramics comprising  $\beta$  -quartz ( $\beta$  -SiO<sub>2</sub>) and/or  $\beta$  -quartz solid solution ( $\beta$  -SiO<sub>2</sub> solid solution) as a predominant crystal phase.

- 33. (Original): Glass-ceramics as defined in claim 32 comprising, in mass %, Li<sub>2</sub>O within a range of 3.5-4.5%.
- 34. (Previously presented): Glass-ceramics as defined in claim 33 comprising, in mass %,

CaO	0.5-1.5% and
MgO	0.5-1.5% and/or
ZnO	0.1-1.5% and/or
BaQ	0.5-1.5% and/or
TiO <sub>2</sub>	1.5-3.0% and/or
ZrO <sub>2</sub>	1.0-3.0% and/or
As aOa	0.5-1.0%